

*ABSTRACT AMENDMENTS*

Replace the Abstract with:

A resist is ~~stacked~~ on a substrate with a lower layer film ~~in~~ between the resist and the substrate. The lower layer film ~~is composed in such a way that includes chemical elements and the element absorbing the largest amount of x-rays of all the elements contained here is the element C carbon~~. The ~~film~~ thickness of the lower layer film is determined by considering the ~~influence influences~~ of secondary electrons from the substrate and ~~that of the element C carbon~~ of the lower layer film. The resist ~~has added thereto an element Cl includes chlorine~~, or a similar element, having a specific absorption edge. Under such conditions, ~~x-rays are irradiated such that the average wavelength of x-rays absorbed in the resist is in a prescribed range. In this way, in x-ray exposure can be performed while, blur caused by secondary electrons is suppressed using a wavelength region of relatively shorter wavelengths.~~